

Customer A
Performance Data:
+0.062% Eff
compared to baseline

ltem	Uoc	Isc	Rs	Rsh	FF	Eta	lrev2	
Baseline	0	0	0	0	0	0	0	
SunFonergy	0.0015	0.014	0.05	101	-0.05	0.062	-0.017	

Customer B
Performance Data:
+0.08% Eff compared
to baseline

ltem	Uoc	Isc	Rs	Rsh	FF	Eta	Pmpp
Baseline	0	0	0	0	0	0	O
SunFonergy	1.5	0.002	- 0.04	34	0.09	0.08	0.019





Increases efficiency;

SunFonergy's SPO thoroughly remove the residues after texturing and etching, and disperse residues away from wafer surface, than increases cell efficiency.



High compatibility;

No change to the present equipment and production process.